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## Generalization of the One Dimensional Modeling and Design Considerations of Spiral Si Drift Detectors: Flat (Straight) Drift Channels and Constant Drift Fields

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The one-dimensional design consideration for the spiral (cylindrical geometry) Si drift detector (SDD) described in literature [1-2] has been modified and generalized for small drift distance ( $R$ ) compatible to the detector thickness ( $d$ ), i.e. for  $R \sim d$ , and for non uniform backside biasing situations. With smaller  $R$ , an array of SDD with small pixel size down to a few hundreds of microns will be possible. Also, by applying a non uniform biasing voltage with a gradient similar (proportional) to the front side, one can increase the reach-through voltage, resulting in a large drift field for carriers. This can be important for large  $R$  ( $> 3\text{mm}$ ), or for high resistivity Si substrates ( $> 8\text{ k}\Omega\text{ cm}$ ). In the modeling, the one-dimensional solution to solve the electric potential and drift field, as well as the spiral design have been modified and generalized for all cases. With a careful design of electric field profiles on both sides, one can obtain the optimum case of a spiral SDD with a straight (flat) drift channel and constant drift field throughout the carrier drift channel. The previous solution in the literature is an approximation of this work for  $R \gg d$  and with a curved drift channel.

**Primary author:** Prof. LI, Zheng (Xiangtan University, Xiangtan, China)

**Presenter:** Prof. LI, Zheng (Xiangtan University, Xiangtan, China)

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